

Title (en)

TREATMENT OF OXIDABLE GAS GENERATED FROM WASTE AT A DUMPING AREA

Title (de)

BEHANDLUNG VON OXIDIERBAREM DEPONIEGAS

Title (fr)

TRAITEMENT DE GAZ OXYDABLES PROVENANT DE DECHETS DANS UNE ZONE DE DEVERSEMENT

Publication

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Application

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Abstract (en)

[origin: WO0117701A1] The invention relates to the method for treating oxidable gas generated from waste at a dumping area and to the structure of the dumping area constructed for the method. As the dumping area has been filled up, the organic waste layer (1) is covered with a sealing layer (2) preventing the absorption of water and with an overlying layer, typically a drying layer (3) and a surface layer (4). In oxygen-free conditions in the waste layer (1), oxidable gas, mainly methane, is generated, which is, according to the invention, directed in a self-operated manner through the penetration aperture (10) formed to the sealing layer and made to spread in the lateral direction with the help of one or several flow controllers so that the gas ends in the surface layer (4), in which it becomes biologically oxidised because of the effect of microbes. The penetration aperture may be formed of the well (10) provided with the cover (11), and the gas flow controllers may be perforated pipes (12) extending radially from the side of the well. The oxidation of gas may be intensified by directing air and/or moisture from the piping (15) to the surface layer (4).

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